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(71) Applicant: **TOPPAN PRINTING CO LTD**

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(72) Inventor: **SUGAMA ERIKO**
TAMURA AKIRA

(54) POSITIVE TYPE PHOTO-RESIST COMPOSITION

(57) Abstract:

PURPOSE: To provide a positive type photo-resist composition having high sensitivity and excellent preservation stability and preventing the occurrence of foreign matter with the passage of time when it is used as a solution by adding an acid compound to a 1,2-naphthoquinone azide photosensitive agent and an alkali-soluble resin.

CONSTITUTION: An acid compound is added to a positive type photo-resist composition containing an alkali-soluble resin and a 1,2-naphthoquinone azide

photosensitive agent. This acid compound is an organic acid such as p- toluenesulfonic acid, acetic acid, oxalic acid, or phosphoric acid or an inorganic acid such as hydrochloric acid, nitric acid, or sulfuric acid. The content of the acid compound is set to 0.05-1wt.% against the photo-resist composition. The resist is soluble in alkali when exposed, however the photosensitive agent is deposited as foreign matter in an alkaline solution when it is not exposed, thus the solution is made to be on slightly acid side to neutral so that foreign matter is hardly deposited.

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